

APPLICANT: YANG, TSUN-NEG

SERIAL NO.: 10/715,982 ART UNIT: 2881

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TITLE: ION IMPLANTING APPARATUS

AMENDMENT "A"

Amendment A: ABSTRACT AMENDMENTS

On page 15, please revise the Abstract as follows:

Please cancel Claims 1 - 13 and substitute Claims 14 - 20 therefor as follows:

The An ion implanting apparatus of the present invention comprises has a wafer cassette capable of loading a plurality of wafers, an implanting chamber including an implanting base, a cassette-transferring module for moving the wafer cassette, and a wafer-transferring module for moving the wafer from the wafer cassette to the implanting base. The wafer cassette comprises has a plurality of irradiation tray trays for loading the wafer, while the implanting base comprises has a guiding slot for guiding the irradiation tray. The cassette-transferring module comprises includes a rack positioned on the wafer cassette, a gear for moving the wafer cassette by driving the rack through rotating, and a first stepping motor for driving the gear. The wafer-transferring module comprises has a push plate for moving the irradiation tray from the wafer cassette to the implanting base, and a second stepping motor for driving the push plate.